

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Yohei YAMAZAWA, et al.

SERIAL NO: NEW APPLICATION

GAU:

FILED: HEREWITH

EXAMINER:

FOR: PLASMA PROCESSING APPARATUS

**INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97**

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

Applicant(s) wish to disclose the following information.

**REFERENCES**

- ☒ The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

**RELATED CASES**

- ☐ Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

**CERTIFICATION**

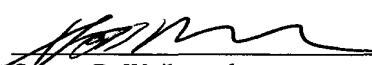
- ☐ Each item of information contained in this information disclosure statement was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- ☐ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

**DEPOSIT ACCOUNT**

- ☒ Please charge any additional fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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**STATEMENT OF RELEVANCY**

**AO: 2000-286235** This document discloses a plasma processing apparatus comprising a means for adjusting the impedance of a return current circuit. The return current circuit extends from a plasma, passes at least a chamber inner wall and returns to a high frequency power supply.

**AP: 2002-343768** This document discloses a plasma processing apparatus comprising: a susceptor; an electric field generating means located at a position opposing the susceptor; and a filter, located between the susceptor and a GND point, for optimally changing circuit characteristics.

**AQ: 7-297175** This document discloses a plasma processing apparatus wherein power with a relatively low frequency and power with a relatively high frequency are applied to opposing first and second electrodes through respective matching devices. An impedance component having an impedance value within a predetermined range is inserted between a GND point and a point where each electrode is connected to the corresponding matching device.

**AR: 11-185998** This document discloses a plasma processing apparatus comprising: a plasma excitation electrode; a susceptor electrode; and a resonation circuit which performs series resonance with a cubic circuit including at least the susceptor electrode and a processing chamber.

**AS: 58-158929** This document discloses a plasma processing apparatus comprising a pair of parallel planar electrodes. One of the electrodes is applied with high-frequency power, and the other electrode is grounded through a variable reactance element.

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. <b>227430US26</b>		SERIAL NO. <b>NEW APPLICATION</b>	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT <b>Yohei YAMAZAWA, et al.</b>			
				FILING DATE <b>HEREWITH</b>		GROUP	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA	6,485,602	11/26/2002	Hirose			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES                      NO		
	AO	2000-286235	10/13/2000	Japan			X
	AP	2002-343768	11/29/2002	Japan			X
	AQ	7-297175	11/10/1995	Japan			X
	AR	11-185998	07/09/1999	Japan			X
	AS	58-158929	09/21/1983	Japan			X
	AT						
	AU						
	AV						
<b>OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)</b>							
	AW						
	AX						
	AY						
	AZ					<input type="checkbox"/> Additional References sheet(s) attached	
Examiner					Date Considered		
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							